По вопросам продаж и поддержки обращайтесь:

Алматы (7273)495-231 Архангельск (8182)63-90-72 Астрахань (8512)99-46-04 Барнаул (3852)73-04-60 Белгород (4722)40-23-64 Брянск (4832)59-03-52 Владивосток (423)249-28-31 Волгоград (844)278-03-48 Вологда (8172)26-41-59 Воронеж (473)204-51-73 Екатеринбург (343)384-55-89 Иваново (4932)77-34-06 Ижевск (3412)26-03-58 Иркутск (395)279-98-46 Казань (843)206-01-48 Калининград (4012)72-03-81 Калуга (4842)92-23-67 Кемерово (3842)65-04-62 Киров (8332)68-02-04 Краснодар (861)203-40-90 Красноярск (391)204-63-61 Курск (4712)77-13-04 Липецк (4742)52-20-81 Магнитогорск (3519)55-03-13 Москва (495)268-04-70 Мурманск (8152)59-64-93 Набережные Челны (8552)20-53-41 Нижний Новгород (831)429-08-12

Киргизия (996)312-96-26-47

Новокузнецк (3843)20-46-81 Новосибирск (383)227-86-73 Омск (3812)21-46-40 Орел (4862)44-53-42 Оренбург (3532)37-68-04 Пенза (8412)22-31-16 Пермь (342)205-81-47 Ростов-на-Дону (863)308-18-15 Рязань (4912)46-61-64 Самара (846)206-03-16 Санкт-Петербург (812)309-46-40 Саратов (845)249-38-78 Севастополь (8692)22-31-93 Симферополь (3652)67-13-56

Казахстан (7172)727-132

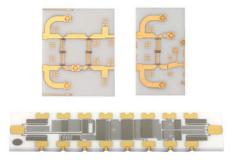
Смоленск (4812)29-41-54 Сочи (862)225-72-31 Ставрополь (8652)20-65-13 Сургут (3462)77-98-35 Тверь (4822)63-31-35 Томск (3822)98-41-53 Тула (4872)74-02-29 Тюмень (3452)66-21-18 Ульяновск (8422)24-23-59 Уфа (347)229-48-12 Хабаровск (4212)92-98-04 Челябинск (351)202-03-61 Череповец (8202)49-02-64 Ярославль (4852)69-52-93

Россия (495)268-04-70

vyh@nt-rt.ru || https://vishay.nt-rt.ru/



Custom Substrates - Metal Via / Multilayer / Lumped Element



FEATURES

- Plated or filled via technology
- Mulitlayer and overcoat patterning
- Lumped element custom substrates
- Al₂O₃, AlN, and BeO substrate drilling and shaping
- TaN and NiCr resistor films
- Metallization on 1,2, or 4 surfaces
- Various substrate materials
- Sputtered / plated metal systems
- Custom sizes from 0.020" x 0.020" to 4.000" x 4.000"
- Quick delivery available

APPLICATIONS

Vishay EFI custom interconnect substrates are used in military, aerospace, hybrid circuit, telecommunications, microwave, and industrial applications. These custom interconnect substrates are manufactured to be used in heat transfer connectors, top to bottom connectors, and RF / microwave designs. Surface connections can be made by plated thru-holes, edge wraps, or filled via technologies. Custom cutouts of various sizes and shapes can also be created and used to fit into almost any size and shape. The custom interconnect substrates are manufactured using Vishay Electro-Films (EFI) sophisticated thin film equipment and manufacturing technology. The custom interconnect substrates are 100 % electrically tested (when applicable) and visually nspected to MIL-STD-883, method 2032 class H or K.



FRONT TO BACK CONTINUITY

For designs requiring metal or electrical connection from the top to the bottom of the substrate, metal via connections will be used. Metalized Edge Wraps are chosen for applications where soldering to the side of the substrate is desired for connection to the PCB or module design. Plated thru-holes are used for applications where the module design may require alignment or soldering pins to be inserted into the holes. Filled vias are used for applications where the strongest electrical connection is needed or preventing solder migration to the backside. See Fig. 1 below for edge wrap, plated thru-hole, and filled via pictorial representation.

METALLIZED EDGE WRAPS		
Min. distance from wrap edge to pattern edge	0.005"	
Min. tolerance from wrap center to pattern edge	± 0.002"	
Wrap diameter (as measured from exit side)	0.8 to 2.0 x substrate thickness	

PLATED THRU-HOLES			
Min. distance from hole edge to pattern edge	0.005"		
Min. tolerance from hole center to pattern edge	± 0.002"		
Hole diameter (as measured from exit side)	0.8 to 2.0 x substrate thickness		
Min. hole center to hole center spacing	2 x hole diameter		

FILLED VIAS				
Min. distance from via edge to pattern edge	0.0025"			
Min. tolerance from via center to pattern edge	± 0.002"			
Min. via center to via center spacing	2 x via diameter			
Preferred via diameter (as measured from exit side)	0.8 x substrate thickness			
Via diameter range (as measured from exit side)	0.6 - 1.5 x substrate thickness			
Min. via diameter	0.007"			
Max. via diameter	0.040"			

Note

· These rules apply to the non-vented via side

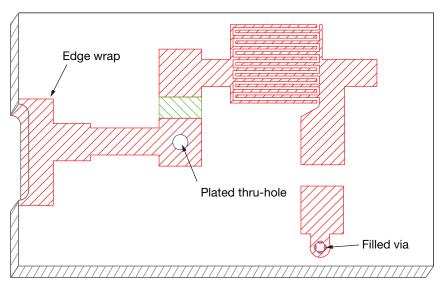


Fig. 1



INT

Vishay Electro-Films

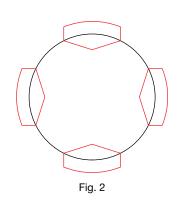
FILLED VIA VENT NOTES

Min. distance from via vent edge to pattern edge

0.004"

Note

- Via vents are required on one side of the substrate if metals are plated
- See Fig. 2 for via vent pattern example



SHAPES AND CUT-OUTS

Many circuit designs require custom substrates with different shapes and holes cutout of the parts. These include cutting out material internal and external to the overall part size and shape.







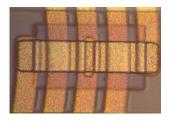
PART SHAPE / CUT-OUTS			
Min. distance from cut-out edge to pattern edge	0.003"		
Min. tolerance from cut-out edge to pattern edge	± 0.002"		
Min. tolerance of cut-out feature	± 0.003"		
Min. distance between cut-outs	0.050"		



MULTILAYER AND AIR BRIDGE

For certain complex designs multiple layers of metal and / or interlevel dielectrics are required. Vishay Electro-Films has developed precision patterning and layering techniques where ± 0.0001 " pattern tolerance and ± 0.0005 " layer to layer alignment is achievable.





For Multilayer designs that require an interlevel dielectric the following two choice are currently available:

DIELECTRIC	IC TYPICAL THICKNESS PATTERN TOLERANCE		DIELECTRIC CONSTANT	
Silicon nitride ⁽¹⁾	4000 Å to 6000 Å	± 0.002"	-	
Polyimide	50 000 Å to 80 000 Å	± 0.002"	3.2 at 1 MHz	

Note

⁽¹⁾ Silicon nitride can also be used to integrate a capacitive element to the design if needed

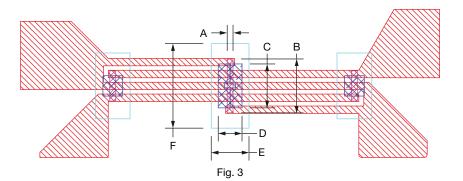
In applications where lange couplers and cross-metal patterning are needed, air bridges can be used to connect different metal patterns using polyimide supported bridges. These bridges require several design guidelines for layering the base metal, polyimide, and bridge metal into the optimum air bridge design.

Fig. 3 can be used as a guideline for a typical lange coupler / air bridge set-up. The dimensions listed in the bubble detail picture are considered minimums for any design. For more specific design layout guidelines, contact the factory for more information.

MULTI-LEVEL CROSSOVER DESIGN PARAMETERS				
PARAMETER		IETER MINIMUM VALUE (in μm)		
Dimension	Crossover thickness	0.0001 (2.5)	Minimum	
А	Crossover width	0.001 (25)	0.0001 in crossover to conductor pullback	
В	Crossover length	0.003 (75)	Minimum	
C/D	Insulator dimension	Length: 0.0015 (37.5) Width: 0.003 (76)	0.0025 (63) insulator-to-conductor overlap	
	Insulator material		Polyimide	
E/F	Encapsulation dimension	Crossover width: +0.0015 (37.5) Crossover length: +0.003 (76)	These values are added to the insulator dimension	
	Encapsulation material		Polyimide	

Note

• These rules apply to the non-vented via side



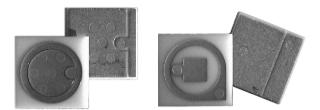
GLOBAL PART NUMB	ER INFORMATION	
Custom Global Part Number:	INT206822-03Q	
Custom Global Part Number	Description: interconnect custom 206822-03Q	
ΙΝΤ	2 0 6 8 2 2 - 0 3	Q
MODEL	INTERNAL P/N	VARIANT
		Q = metalized thru-holes, filled vias, cut-outs, multilayer Z = SLR
Note		

• Z = SLR,

VISHAY



Ceramic Submount for High Power LED



The LSUB series substrates are ceramic LED package bases designed to provide thermal management for high power (> 1 W) LED devices; the LSUB is designed to minimize the thermal resistance between the die junction and the package termination. The LSUB's enhanced thermal management enables a lower junction temperature and increased efficiency and reliability compared to other technologies. In addition to the increased brightness, the lower junction temperature results in better color uniformity.

The LSUB is available in two configurations; in the standard configuration the LED die is mounted directly over filled vias and an offset version where the filled via is located to the side of the die pad. The standard configuration is designed for the attach methods including conductive epoxies and thick solders (greater than 12 μ m) while the offset configuration is designed for thin eutectic solder layers in the 2 μ m to 3 μ m range. An additional benefit of the standard configuration is the pad size is large enough to accommodate a parallel diode for ESD protection.

The LSUB is available singulated as individual die or in square arrays. Additional LED configurations and form factors available upon reques.

FEATURES

- Ultra-low thermal resistance
- Eutectic or epoxy LED die attach pads
- · Surface-mounted component assembly

APPLICATIONS

- High power LED for automotive, industrial and home applications
- High power laser diodes for industrial applications

GENERAL SPECIFICATIONS				
Substrate Material	Alumina 99.6 %, Alumina 96 % or AlN			
Conductor Material	Copper			
Conductor Thickness	5 μm ± 10 %			
Substrate Thickness	25 mil (0.635 mm)			
LED Die Size	40 mil x 40 mil (1 mm x 1 mm)			
Operating Temperature (°C)	- 55 to + 125			
Storage Temperature (°C)	- 55 to + 125			
Die Bond Pad Metallization	Ni/Au or 80 %/20 % AuSn over Ni/Au			

TYPICAL THERMAL RESISTANCE ⁽¹⁾ (K/W)				
SUBSTRATE STANDARD OFFSET				
AIN 3 5		5		
Alumina (99.6 %)	6	8		
Alumina (96 %) 10 12				

Note

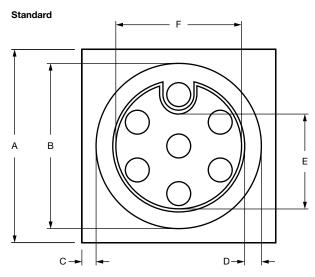
⁽¹⁾ Thermal resistance between die pad and package termination (anode)

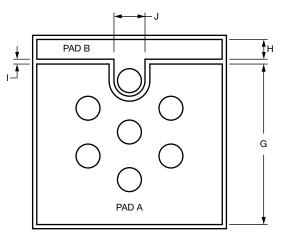


Ceramic Submount for High Power LED

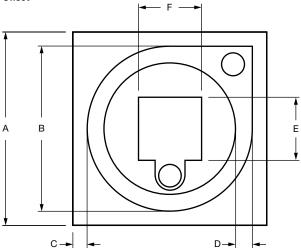
Vishay Electro-Films

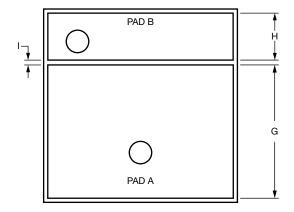
DIMENSIONS





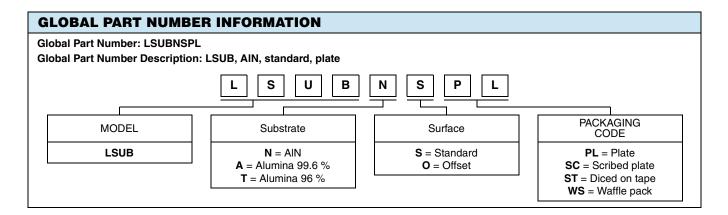
Offset





DIMENSIONS in inches (millimeters)				
DIMENSION	STANDARD	OFFSET		
A	0.138 (3.500)	0.138 (3.500)		
В	0.118 (3.000)	0.118 (3.000)		
С	0.010 (0.254)	0.010 (0.254)		
D	0.012 (0.300)	0.012 (0.300)		
E	0.068 (1.727)	0.045 (1.143)		
F	0.090 (2.286)	0.045 (1.143)		
G	0.114 (2.896)	0.095 (2.413)		
н	0.014 (0.356)	0.033 (0.838)		
I	0.003 (0.076)	0.003 (0.076)		
J	0.016 (0.406)	n/a		





LAYOUT CONSIDERATIONS

The thermal performance of the LSUB package is strongly influenced by PCB layout. The package ensures that heat flows from the die junction to the package termination (anode); however, the heat must be carried from the termination by the PCB layout. Special consideration must be given to insure minimal thermal resistance between the package termination and the ambient. The following guidelines should be considered.

- The filled vias in the standard configuration can be up to 0.5 mils lower than the surrounding surface, when mounting dies on top of these vias care should be taken to use an attachment method capable of overcoming this surface profile.
- The traces that carry current to and from the component also carry the heat away from the component. These traces should be made as wide and thick as possible to help spread the heat on the PCB.
- The LED die should be kept as far as possible from other hot components such as DC circuitry, FETs and inductors.
- Heat sink elements are to be positioned as closely as possible to the LED package.



Custom Substrates - Conductor Resistor Pattern and Overcoat



FEATURES

- Precision conductor and resistor patterns
- TaN and NiCr resistor films
- Resistor tolerance down to 0.1 %
- · Silicon nitirde, and polyimide overcoat coatings
- Metallization on 1 or 2 surfaces
- Various substrate materials
- Sputtered / plated metal systems
- Custom sizes from 0.020" x 0.020" to 4.000" x 4.000"
- Quick delivery available

APPLICATIONS

Vishay EFI conductor resistor patterned substrates with optional overcoat coatings are used in the hybrid circuit, microwave, and telecommunications industries. These conductor resistor patterns are precisely manufactured to be used for precision current flow, voltage division and RF / Microwave designs. Resistor overcoat options are used for resistor protection and can be applied and patterned to match the conductor and / or resistor pattern. The conductor resistor patterned substrates are manufactured using Vishay Electro-Films (EFI) sophisticated thin film equipment and manufacturing technology. The custom specialty film substrates are visually inspected to MIL-STD-883, method 2032 class H or K.

INTEGRATING THIN FILM RESISTORS

Vishay EFI offers two thin film resistor film choices of lithographically patterned Tantalum Nitride (TaN) or Nickel Chromium (NiCr). The resistive film should be selected based upon application-specific requirements such as performance, assembly packaging needs, and temperature exposure. The table below summarizes the key standard parameters of these resistor materials.

STANDARD THIN FILM RESISTOR PARAMETERS					
MATERIAL	TCR (ppm/°C)	STANDARD SHEET RESISTIVITY 99.6 % Al ₂ O ₃ (Ω/sq)	STANDARD SHEET RESISTIVITY AIN, BeO (Ω/sq)	STABILITY ⁽¹⁾	TOLERANCE ⁽²⁾
TaN	± 50	20 to 125	25 to 100	< 0.1 %	0.1 % to 20 %
NiCr	± 25	25 to 225	50 to 150	< 0.1 %	0.1 % to 20 %

Notes

⁽¹⁾ 1000 h at 125 °C in air

⁽²⁾ Special tolerances available



CURRENT DENSITY

To ensure optimal Resistor performance, the design engineer must consider the self-heating effects of the operating resistor and understand the power dissipation characteristics of the environment. A complete thermal analysis should be performed by the design engineer to ensure proper thin film resistor design. The following table lists current density standards for common materials.

CURRENT DENSITY					
SHEET RESISTANCE	Al ₂ O ₃	SILICON	QUARTZ	AIN	BeO
25 Ω/sq	4 mA/mil	20 mA/mil	0.5 mA/mil	19 mA/mil	32 mA/mil
50 Ω/sq	2 mA/mil	10 mA/mil	0.25 mA/mil	9.5 mA/mil	16 mA/mil
100 Ω/sq	1 mA/mil	5 mA/mil	0.125 mA/mil	4.7 mA/mil	8 mA/mil
200 Ω/sq	0.5 mA/mil	2.5 mA/mil	0.062 mA/mil	2.3 mA/mil	4 mA/mil

RESISTOR DESIGN

After the thin film resistor values have been determined and a metallization film selected per SPF1 and SPF2 datasheets, the thin film resistor layout can be designed. There are two typical approaches for accomplishing this: the block-style resistor (see Fig. 1) or serpentine- style resistor (see Fig. 2). With both design approaches, it is standard to employ a laser trim process to trim the resistor to the desired value and tolerance. Vishay EFI employs both scrub (edge) trimming and plunge trimming techniques to achieve the desired resistor value.

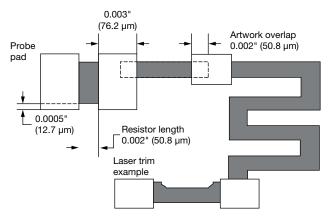


Fig. 1 - Probe pad and artwork overlap requirements (minimum)

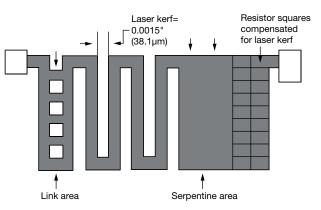


Fig. 2 - Serpentine resistor with two areas for laser trim

RESISTOR DESIGN RULES						
PARAMETER	VALUES	COMMENTS				
Min. resistor dimension	0.002" x 0.002" (50 μm x 50 μm)					
Min. probe pad dimension	0.003" x 0.003" (75 μm x 127 μm)	For resistors < 1000 Ω, use probe pad size of 0.006" (152 μm) x 0.008" (203 μm)				
Min. conductor/resistor design overlap	0.002" (50 μm)	See Fig. 1				
Resistor layout dimensions (block resistor/serpentine resistor)	100 % of nominal value / 100 % of nominal resistor value plus laser kerfs of 0.5 mil ² /sq					
Resistor trim	Scrub, plunge, or bake to value	Bake to value ± 10 % or 20 %				

All high frequency resistors should be Edge trimmed to value to preserve frequency response. VEFI can also supply resistors of 20 % tolerance (10 % special) or looser tolerances which are designed to 100 % of bake to value with no laser trimming.



PROTECTIVE COATING

Vishay Electro-Films (EFI) has developed several patternable overcoat options to protect the resistors and other critical areas from mechanical damage during handling. It is essential to overcoat resistors of 0.1 % or tighter tolerances to maintain tolerance during assembly and test of the hybrid, and it is beneficial to overcoat all resistors.

PROTECTIVE COATING APPLICATIONS					
OVERCOAT TYPICAL THICKNESS (Å) APPLICATIONS					
Silicone nitride	4000 to 6000	Resistor overcoat with fine trim capability and integrated capacitor			
Polyimide	50 000 to 80 000	Resistor overcoat and solder dam			

PROTECTIVE COATING GUIDELINES							
OVERCOAT	RCOAT TYPICAL THICKNESS (Å) MIN. FEATURE SIZE MIN. METAL OVERLAP PATTERN TOLERA						
Silicone nitride	4000 to 6000	0.004" x 0.004"	0.002"	± 0.002"			
Polyimide	50 000 to 80 000	0.004" x 0.004" ⁽²⁾	0.001"	± 0.002"			

Notes

 $^{(1)}$ Special tolerance of \pm 0.001" available

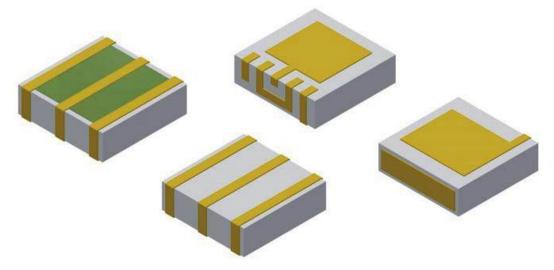
⁽²⁾ Minimum gap in polyimide pattern is 0.0015" x 0.003"

In summary NiCr will perform at higher sheet resistance with lower TCR than TaN giving higher resistance values in less area. TaN will continue to perform in a moisture environment but NiCr will require a hermetic package to maintain resistance values. Both resistive films will work in highly demanding environments for a wide range of applications with VEFI thin film technology.

GLOBAL PART NUMBER INFORMATION							
Custom Global Part Number:	PSS205687-00N						
Custom Global Part Number	Description: Specialty Films Custom 205687-00N						
P S S	2 0 5 6 8 7 - 0 0	Ν					
MODEL	CUSTOM PART NUMBER INTERNAL REVISION	VARIANT					
		$\mathbf{A} = AIN$					
		B = BeO F = ferrite/					
		garnet					
		K = zirconia N = resistor					
		conductor					
		3					



Side Wall Patterning - Custom Substrate



CAPABILITIES

- Conductor patterning on 4 surfaces
- Wire-bondable or solderable metalizations
- · Allows attachment to side wall of substrate
- Tight dimensional tolerances

APPLICATIONS

- Electro-mechanical or electro-optical applications that require an interface between the electric circuit and an element such as a mirror, lens, fiber, etc.
- High frequency circuits such as RF application, and high bit rate transceivers (TOSA / ROSA) that benefit by replacing wire bonds with side-patterned traces
- Applications that require a high degree of miniaturization

DESIGN SPECIFICATIONS AND RULES

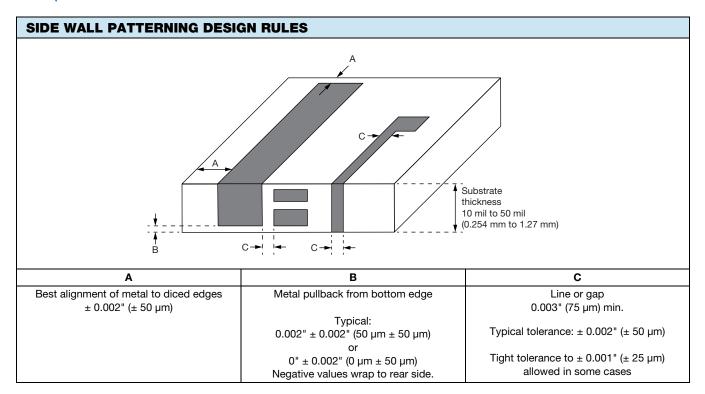
- Substrate materials: alumina or AIN. Sidewall patterning can be deposited on plates ranging between 10 mils and 50 mils. Polished plates are preferred due to their tighter thickness tolerance.
- Metalization: TiW / Au, TiW / Ni / Au or TiW / Pd / Au as well as resistor and AuSn metalization available.
- Lines and gaps: lines and gaps down to 0.003" (75 microns) can be patterned on the component sidewalls.
- Pullback from bottom edge: traces designed to reach the bottom edge of the sidewall will requires a ± 2 mil tolerance. Positive tolerance represents a gap from the bottom edge; negative tolerance represents metal wrapping around edge to the rear surface.
- Geometric tolerances down to ± 1 mil (± 25 μm) can be maintained on sidewall geometries. Tolerances between metal on diced edges of the ceramic tile down to ± 2 mil.
- Connectivity: side wall patterns can be isolated (standalone), connected to front side only (half wrap) or connected to both front and rear sides (full wrap).
- Component with sidewall patterning can have integrated resistors or AuSn solder pads embedded on the front or rear surfaces. These capabilities are not allowed on the sidewall itself.

DESIGN SPECIFICATIONS					
Plate Thickness	0.010" to 0.050"				
Minimum Gap	0.003"				
Dimensional Tolerance	± 0.001"				
Metal Pattern to Diced Edge Tolerance	≥ 0.002"				
	TiW / Au / Au plate or TiW / Pd / Au				
Motol Systems	TiW / Au / Ni plate / Au plate				
Metal Systems	TaN / TiW / Au or NiCr / TiW / Au				
	80 / 20 AuSn pads available, consult factory				



SDWP

Vishay Electro-Films



GLOBAL PART NUMBER INFORMATION								
Global Part Numbering example: SDW	/P20xxxx-00Q							
S D W P		Q						
Model Sequential: assigned by factory Internal revision								



SPF1

Vishay Electro-Films

Thin Film Metallized Plates - Custom Substrates



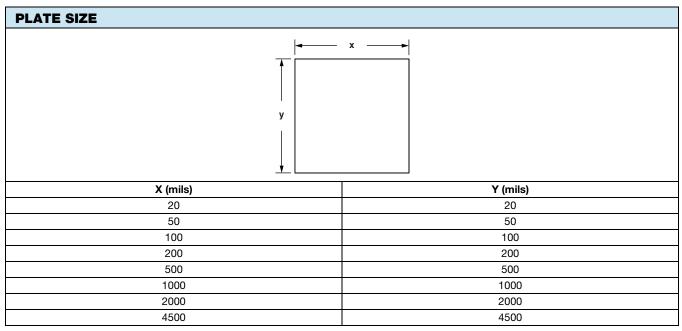
FEATURES

- Metalization on 1, 2, or 6 surfaces
- Various substrate materials
- Tantalum nitride or nickel chromium resistor material
- Sputtered / plated metal systems
- Sizes from 0.020" x 0.020" to 4.500" x 4.500"
- High volume
- Quick delivery available

APPLICATIONS

Vishay EFI metalized plates can be used as stand-offs, jumpers or bonding pads in hybrid packages when diced to small sizes; they are also available with no metallization (bare ceramic) for use as spacers or insulators. Larger sized plates can be used where the customer wants to pattern and etch substrates in-house.

SUBSTRATE MATERIALS						
MATERIAL CODE	MATERIAL		SURFACE FINISH (μ" CLA)	APPLICATION		
		А	< 3 front / < 4 back as-fired			
А	Alumina (99.6)	L	< 12 lapped	Cost effective material with wide range of applications		
		Р	< 1 polished	range of applications		
В	Don Ilium ovido	L	15 to 40 lapped	Highest thermal conductivity		
В	Beryllium oxide	Р	< 3 polished	(285 W/mC)		
N	Aluminum nitride	L	10 to 20 lapped	High thermal conductivity		
IN	Auminum nitride	Р	< 2 polished	(170 W/mC)		



Note

• For any plates smaller than 1.000" x 1.000" or where plate size is not available, metal is only available on one or two surfaces (front or back)



RESISTOR MATERIAL

Typical reasons for using NiCr resistor material are for long term stability and high sheet rho. Typical recommended uses for TaN are for non-hermetic applications where self-passivation is important.

RESISTOR MATERIAL							
RESISTOR CODE	RESISTOR MATERIAL	SHEET RHO (Ω/SQ) ± 20 %	TCR (ppm/°C) TYPICAL VALUES				
A	NiCr	25	± 50				
В	NiCr	50	± 100				
С	NiCr	100	± 200				
D	NiCr	200	± 250				
1	TaN	25	± 50				
2	TaN	50	± 100				
3	TaN	75	± 250				

META	METAL STACK							
METAL CODE	METAL STACK	TYPICAL APPLICATION	TYPICAL ATTACHMENT METHOD					
1	TiW (500 Å to 1000 Å) / Au (50 μ" min.)	Au and Al wirebondable	Ероху					
2	TiW (500 Å to 1000 Å) / Au (100 μ" min.)	Au and Al wirebondable	Ероху					
3	TiW (500 Å to 1000 Å) / Au (15 μ" to 40 μ") / Ni (20 μ" to 80 μ") / Au (50 μ" min.)	Au and Al wirebondable and solderable	Epoxy or solder					
4	TiW (500 Å to 1000 Å) / Au (15 μ " to 40 μ ") / Ni (20 μ " to 80 μ ") / Au (100 μ " min.)	Au and Al wirebondable and solderable	Epoxy or solder					
5	TiW (500 Å to 1000 Å) / Pd (1500 Å to 2500 Å) / Au (50 μ" min.)	Au and Al wirebondable and solderable	Epoxy or solder					
6	TiW (500 Å to 1000 Å) / Pd (1500 Å to 2500 Å) / Au (100 μ" min.)	Au and Al wirebondable and solderable	Epoxy or solder					
7	Cr (500 Å to 1500 Å) / Cu (5000 Å to 7000 Å) / Au (100 μ" min.)	Au and Al wirebondable	Ероху					
8	Cr (500 Å to 1500 Å) / Cu (500 u" min.) / Ni (20 μ" to 80 μ") / Au (100 μ" min.)	Au and Al wirebondable and solderable. High power applications for low metal resistivity	Epoxy or solder					



VISUAL INSPECTION

VEFI uses internal visual inspection criteria as shown in the table below for metal non-patterned substrates. For any plates smaller than 1.000" x 1.000" or where plate size is not available, metal burrs will be acceptable along part edges where plates are sawn to size.

SCHEMATIC ILLUSTRATION	DEFECT TYPE	DEFECT SIZE	FRONT ⁽²⁾	BACK ⁽³⁾
		> 10 mil dia. (>0.254 mm)	0.25/sq"	0.25/sq"
anima		5 mil to 10 mil dia. (0.127 mm to 0.254 mm)	1/sq"	2/sq"
Metallization (NODULES BUMPS	3 mil to 5 mil dia. (0.076 mm to 0.127 mm)	3/sq"	6/sq"
Akimina (1965)		2 mil to 3 mil dia. (0.05 mm to 0.076 mm)	3/sq"	6/sq"
		< 2 mil dia. (< 0.05 mm)	NIF	NIF
		> 2 mil dia. (> 0.05 mm)	None	None
Conductor	METALIZATION VOIDS PINHOLES	1 mil to 2 mil dia. (0.0254 mm to 0.05 mm)	5/sq"	10/sq"
[W. Alumina Web]]	FINIOLES	< 1 mil high (< 0.0254 mm)	NIF	NIF
		> 10 mil dia. (> 0.254 mm)	None	None
Metallization-	CRATERS	5 mil to 10 mil dia. (0.127 mm to 0.254 mm)	1/sq"	3/sq"
	DEPRESSIONS (hole into	2 mil to 5 mil dia. (0.05 mm to 0.127 mm)	4/sq"	4/sq"
A humuna	ceramic)	1 mil to 2 mil dia. (0.0254 mm to 0.05 mm)	15/sq"	15/sq"
		< 1 mil dia. (0.0254 mm)	NIF	NIF
Penetrates Underlying Layer	SCRATCHES ⁽⁴⁾ (excluding	> 1/2 mil wide (> 0.0127 mm)	1/sq"	NIF
Conductor	surface abrasions)	< 1/2 mil wide (< 0.0127 mm)	NIF	NIF
		> 10 mil dia. (> 0.254 mm)	None	None
		5 mil to 10 mil dia. (0.127 mm to 0.254 mm)	1/sq"	1/sq"
		2 mil to 5 mil dia. (0.05 mm to 0.127 mm)	2/sq"	2/sq"
Conductor	BLISTERS	1 mil to 2 mil dia. (0.0254 mm to 0.05 mm)	4/sq"	4/sq"
Abumina [1/2 mil to 1 mil dia. (0.0127 mm to 0.0254 mm)	6/sq"	6/sq"
		1/4 mil to 1/2 mil dia. (0.006 mm to 0.0127 mm)	16/sq"	16/sq"
		< 1/4 mil dia. (< 0.006 mm)	NIF	NIF
		> 4 mil. (> 0.1 mm)	None	None
04	STAINS-SPOTS (5)	2 mil to 4 mil (0.05 mm to 0.1 mm)	1/sq"	2/sq"
Stains	31AIN3-3PU13 (0)	1 mil to 2 mil (0.0254 mm to 0.05 mm)	2/sq"	4/sq"
L		< 1 mil (< 0.0254 mm)	3/sq"	5/sq"

Notes

• NIF = not inspected for

⁽¹⁾ Exclusion area for 1" x 1" and greater plates: Front and Rear: 100 mils (2.54 mm) from substrate edge

(2) A-face 100 % inspection method: 3x to 8x magnification. Higher magnification may be used for defect verification

⁽³⁾ B-face 100 % inspection method: Unaided eye. Higher magnification may be used for defect verification

- $^{(4)}\,$ Scratch or probe mark exposing underlying material that is >200 mils long
- ⁽⁵⁾ Contamination: Not removable by distilled water or common solvents



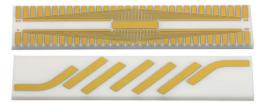
GLOBAL PAR	GLOBAL PART NUMBER INFORMATION							
Standard Global Part Number: SPF1AA02021A11BX								
Global Part Numbe	er Descriptio			s-Fired 20 mils (50 μ" min.) Β		nils Thick NiCr 2	$\overline{\mathfrak{o}} \ \Omega/sq $ Front: TiW / A	u (50 μ" min.)
S P F	: 1	Α	Α	0 1	0 1	1 1 A	1 1	ВХ
MODEL MATERIAL	FINISH	PLATE SIZE X (MILS)	PLATE SIZE Y (MILS)	THICKNESS (MILS)	RESISTOR	METAL FRONT	METAL BACK	PACKAGING CODE
SPF1 A = Al ₂ O ₃ B = BeO N = AIN	A = as-fired L = lapped P = polished	02 = 20 05 = 50 10 = 100 20 = 200 50 = 500 11 = 1000 21 = 2000 45 = 4500	02 = 20 05 = 50 10 = 100 20 = 200 50 = 500 11 = 1000 21 = 2000 45 = 4500	1 = 10 2 = 15 3 = 20 4 = 25	N = none Otherwise see Resistor Material table	N = none Otherwise see Metal Stack table	N = none Otherwise see Metal Stack table	BX = box 1 min. / 1 mult. W1 = waffle pack 1 min. / 1 mult.
Custom Global Par	rt Number: S	SPF1 xxxx	- xx x					
S P MOD	EL	1		VEFI ASSIGN	ED NUMBER		INTERNAL REVISION	VARIANT A = ALN B = Be0 0 = coating

Note

• Plates 1" x 1" and greater will be individually packaged in glassine envelopes in the box



Custom Substrates - Conductor Pattern



FEATURES

- Precision conductor patterns
- Metalization on 1 or 2 surfaces
- Various substrate materials
- Sputtered / plated metal systems
- Custom sizes from 0.020" x 0.020" to 4.000" x 4.000"
- Quick delivery available

APPLICATIONS

Vishay EFI custom specialty films / conductor patterned substrates are used in the hybrid circuit and microwave industries. These conductor patterns are precisely manufactured to be used for complex fan-outs, interconnects, high temperature, and RF / microwave designs. Vishay EFI custom specialty films / conductor patterned substrates can also be used in a wider variety of applications including jumpers, mounting pads, and bonding pads. The custom specialty film / conductor patterned substrates are manufactured using Vishay Electro-Films (EFI) sophisticated thin film equipment and manufacturing technology. The custom specialty film / conductor patterned substrates are visually inspected to MIL-STD-883, method 2032 class H or K.

DEFINING A METAL SYSTEM

Vishay EFI offers several different metals to meet the custom needs of our customers. Simple conductor circuits have the most flexibility with available metal systems. As the complexity and level of integration increase, the list of available metal system choices is limited to allow for tighter process control and manufacturability. The following table identifies the specific function of the available metals as well as their available thickness ranges.

AVAILABLE METALS AND THEIR FUNCTIONS							
LAYER TYPE	METAL	METAL RANGE OF VALUES					
Adhasian	Titanium tungsten (TiW)	500 Å to 1250 Å	Ideal for high temperatures				
Adhesion	Chromium (Cr)	500 Å to 1250 Å	Ideal for low temperatures				
Barrier	Nickel (Ni)	1250 Å to 1750 Å	Sputtered barrier				
Darrier	Palladium (Pd)	1500 Å to 2500 Å	High temperature solder barrier				
	Gold (Au)	10 μ" to 200 μ" (0.25 μm to 5 μm)	-				
Conductor	Copper (Cu)	20 μ" to 200 μ" (0.05 μm to 5 μm)	-				
	Aluminum (Al)	50 μ" to 120 μ" (1.27 μm to 5 μm)	Aluminum wire bond				
High Current Conductor	Gold (Au)	200 μ" to 1000 μ" (5 μm to 25 μm)	Gold wire bond				
High Current Conductor	Copper (Cu)	200 μ" to 4000 μ" (5 μm to 100 μm)	High temperature / conductivity				

Note

• TaN and NiCr are available as adhesion metal layers under certain metal stacks. Call factory for details





APPLICATION OF METAL SYSTEMS

A metal system should be selected based upon electrical, thermal, and mechanical performance demands as well as the assembly process requirements. Assembly requirements might include pads suitable for eutectic (solder) bonding and / or wire bonding.

Soldering pads should include a barrier layer designed to control the solubility of the pad metallization with the solder being applied. A nickel or palladium barrier layer is typically deposited under gold soldering pads to ensure reliable device attachment due to gold's high solubility in solders.

All of the standard metal systems offered by Vishay EFI are readily bonded using gold wire. For optimal bond integrity, a minimum of 100 μ " (2.5 μ m) gold thickness is recommended, although reasonable bonding results can be achieved with gold as thin as 50 μ " (1.2 μ m).

Intermetallic formation and barrier metal migration are influenced by film exposure to high temperatures. For this reason, it is important to select a metal system that can withstand the temperature profile requirements of the application. The following table provides a matrix of standard metal systems and assembly options.

STANDARD METAL SYSTEMS AND ASSEMBLY OPTIONS				
METAL SYSTEM	MAX. REFLOW TEMPERATURE	WIRE-BONDABLE GOLD	SOLDER TYPE	
			LEAD / LEAD (Pb)-FREE	GOLD BEARING
Cr / Cu / Ni / Au	350	Yes	Preferred	Yes
NiCr / TiW / Au	400	Yes	-	Yes
NiCr / Ni / Au	350	Yes	Preferred	Yes
NiCr / TiW / Au / Ni / Au	350	Yes	Preferred	Yes
TiW / Au	450	Yes	-	Yes
TiW / Ni / Au	350	Yes	Preferred	Yes
TiW / Au / Ni / Au	350	Yes	Preferred	Yes
TiW / Pd / Au	450	Yes	Yes	Preferred
TiW / Au / Cu / Ni / Au	350	Yes	Preferred	Yes
TaN / TiW / Au	450	Yes	-	Yes
TaN / TiW / Ni / Au	350	Yes	Preferred	Yes
TaN / TiW / Au / Ni / Au	350	Yes	Preferred	Yes
TaN / TiW / Pd / Au	450	Yes	Yes	Preferred
TaN / TiW / Au / Cu / Ni / Au	350	Yes	Preferred	Yes

Additional metal system capabilities are available. These options are subject to review by the Vishay EFI engineering and production teams. Consideration will be given to special requests, with a focus on manufacturability and reliability.

INCORPORATING HIGH CONDUCTIVITY TRACES

Vishay EFI's capability to deposit thick conductor traces has enabled design approaches that allow high current, low resistance circuit traces to co-exist with microwave structures and transmission lines. For circuit traces carrying high currents over long distances, the resistive losses of thin film conductor lines can become significant. By selectively increasing the thickness of high-current lines, the engineer can have fine line RF structures on the same circuit with low-loss DC lines. Additionally, these low-resistance traces can be used to manage thermal loads within RF circuits.

Typically, the design engineer will calculate the trace resistance (R_{total}) of a structure during the design process. The trace resistance is defined as:

 R_{total} = (trace length / trace width) x conductor sheet resistance

 $R_{\text{total}} = (L / W) \times R_{\text{sheet}}.$

The sheet resistance (R_{sheet}) is derived by dividing the bulk resistivity by the conductor thickness. Therefore, the thicker one can deposit the conductor, the lower the overall sheet resistance. The following two tables detail the bulk resistivity and the typical sheet resistance of some common thin film metals at a variety of deposition thicknesses.



SELECTED BULK RESISTIVITY			
MATERIAL	THEORETICAL BULK RESISTIVITY $\mu\Omega$ x cm	CONSERVATIVE VALUE OF BULK RESISTIVITY WHEN DEPOSITED $\mu\Omega \ \textbf{x} \ \textbf{cm}$	
Gold (Au)	2.2	2.4 (sputtered) / 2.9 (plated)	
Titanium Tungsten (TiW)	-	45 (sputtered)	
Copper (Cu)	1.71	2 (sputtered) / 4 (plated)	
Nickel (Ni)	7	8.2 (sputtered)	
Aluminum (Al)	2.7	3 (sputtered)	

SELECTED APPROXIMATE SHEET RESISTIVITIES			
METAL	THICKNESS μ" (μm)	PLATED SHEET RESISTIVITY (mΩ /sq)	
Gold (Au)	80 (2)	14.5	
Gold (Au)	160 (4)	7.25	
Gold (Au)	400 (10)	2.9	
Copper (Cu)	1000 (25)	0.42	
Copper (Cu)	2000 (50)	0.21	
Nickel (Ni)	200 (5)	160 (sputtered)	
Aluminum (Al)	40 (1)	30 (sputtered)	

In summary, gold (Au) and copper (Cu) can be deposited at much greater thicknesses than standard thin films to reduce overall conductor resistance. Gold (Au) can be deposited up to a maximum thickness of 400 μ ", while copper (Cu) can be plated routinely at thicknesses up to 4000 μ " (100 μ m). It is important to note that minimum line widths and spaces increase with film thickness. See the following for a summary of line widths and spaces as associated with conductor thickness.

PATTERNING LINES AND SPACES

Thin film patterning tolerances are influenced by several factors in the photomasking process. Pattern tolerancing for plating and etching processes vary based on the metal thickness as shown in the tables below. As the thickness of the metal increases, the photoresist used for this process changes and the metal thickness tolerances and line and space patterning must be adjusted to compensate for this. As these decisions are made the surface finish of the substrate must also be factored as the polished surface finish will deliver the smoothest surface and therefore the best line and space pattern. For the substrate materials where As fired and lapped options are available these surfaces will not hold the same tolerances and minimum sizes that the polished surface will.

PLATED METAL PATTERNS				
TOTAL MAX. METAL THICKNESS	BEST PATTERN TOLERANCE PROCESS	BEST PLATING THICKNESS TOLERANCE	SMALLEST PATTERN LINE AND SPACE	
100 μ" (2.54 μm)	± 0.1 mil	± 30 µ"	0.5 mil / 0.5 mil	
150 μ" (3.8 μm)	± 0.15 mil	± 40 μ"	0.5 mil / 0.5 mil	
250 μ" (6.35 μm)	± 0.2 mil	± 50 μ"	0.5 mil / 0.5 mil	
400 μ" (10.2 μm)	± 0.2 mil	± 100 μ"	0.5 mil / 0.5 mil	
800 μ" (20.3 μm)	0.3 mil±	± 150 μ"	1 mil / 1 mil	
1000 μ" (25.4 μm)	± 1.0 mil	± 250 μ"	2 mil / 2 mil	
2000 μ" (51 μm)	± 2.0 mil	± 500 μ"	3 mil / 3 mil	
4000 μ" (102 μm)	± 3.0 mil	± 1 mil	5 mil / 5 mil	



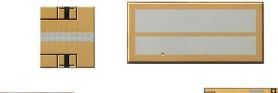
ETCHED METAL PATTERNS				
TOTAL MAX. METAL THICKNESS	BEST PATTERN TOLERANCE PROCESS	BEST METAL THICKNESS TOLERANCE	SMALLEST PATTERN LINE AND SPACE	METAL DEPOSITION
100 μ" (2.54 μm)	± 0.1 mil	Ref. plating table	1 mil / 1 mil	Plated
150 μ" (3.8 μm)	± 0.2 mil	Ref. plating table	1.5 mil / 1.5 mil	Plated
200 μ" (5.1 μm)	± 0.3 mil	Ref. plating table	2 mil / 2 mil	Plated
300 μ" (7.6 μm)	± 0.5 mil	Ref. plating table	2 mil / 2 mil	Plated
12 000 Å	± 0.5 mil	±10 %	1.5 mil / 2 mil	Sputtered
25 000 Å	± 1.0 mil	±10 %	2 mil / 2 mil	Sputtered

AuSn APPLICATIONS

Vishay EFI offers the option of a sputter deposition of gold-tin solder with wt % of 80 / 20 while maintaining tolerances tighter than ± 2 % wt and control of film thickness to ± 1.0 µm. This capability allows deposition of customer AuSn patterns that can be used to fine-tune assembly processes to meet the most demanding requirements; the tight composition tolerance eliminates the need to adjust reflow process parameters to compensate for variations in solder composition. The gold-tin deposition process allows films with thickness ranging between 4.5 µm and 7 µm with a tolerance of ± 1.0 µm. Common applications for AuSn deposition are laser diode sub-mounts, fiber optic pump lasers, optical transmitters, optical receivers, optical transceivers and optical TOSA / ROSA packages.

HIGH TEMPERATURE APPLICATIONS

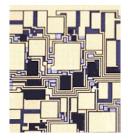
When designing hybrid assemblies to operate at temperatures above 125 °C it becomes important to provide monometallic interconnects to prevent intermetallic diffusion and resultant long term reliability problems. For these situations, Vishay Electro-Films (EFI) has developed processes for depositing both aluminum and gold bonding pads on the same substrate. This structure provides for monometallic interconnects. Aluminum wire can be used to connect from the aluminum pads on the substrate. Similarly, gold wire can be used to connect gold pads on the substrate to gold hermetic package terminals. Appropriate barrier metals are included in substrate processing to provide long term reliability in high temperature applications.











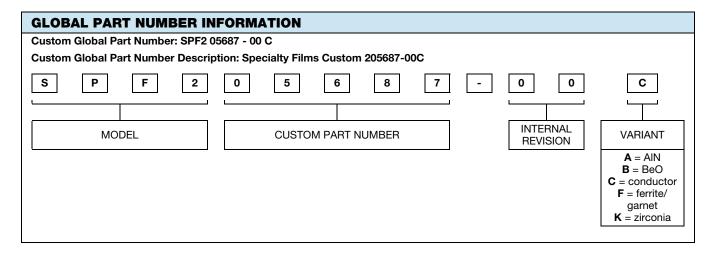
High temperature - Au and Al wirebond pads



SUBSTRATE SINGULATION

Vishay Electro-Films uses standard semiconductor / ceramic dicing equipment and processes to singulate production boards into individual pieces. These processes depend on tight alignment and inspection to maintain overall part dimension tolerances and metal pattern to part edge tolerances. Each of these dimensions and their tolerances are measured on each lot that is processed.

SUBSTRATE SINGULATION			
DIMENSION	DIMENSION MEASUREMENT in inches (mm)	MINIMUM TOLERANCE in inches (mm)	Nominal ± 0.002"
Metal pattern pullback from edge of die	0.002 (0.0508)	± 0.002 (± 0.0508)	Back pattern
Overall part dimension	n/a	± 0.002 (± 0.0508)	
Front to back pattern tolerance	n/a	± 0.002 (± 0.0508)	Front to back pattern registration ± 0.002" (0.051 mm)



По вопросам продаж и поддержки обращайтесь:

Алматы (7273)495-231 Архангельск (8182)63-90-72 Астрахань (8512)99-46-04 Барнаул (3852)73-04-60 Белгород (4722)40-23-64 Брянск (4832)59-03-52 Владивосток (423)249-28-31 Волгоград (844)278-03-48 Вологда (8172)26-41-59 Воронеж (473)204-51-73 Екатеринбург (343)384-55-89 Иваново (4932)77-34-06 Ижевск (3412)26-03-58 Иркутск (395)279-98-46 Казань (843)206-01-48 Калининград (4012)72-03-81 Калуга (4842)92-23-67 Кемерово (3842)65-04-62 Киров (8332)68-02-04 Краснодар (861)203-40-90 Красноярск (391)204-63-61 Курск (4712)77-13-04 Липецк (4742)52-20-81 Магнитогорск (3519)55-03-13 Москва (495)268-04-70 Мурманск (8152)59-64-93 Набережные Челны (8552)20-53-41 Нижний Новгород (831)429-08-12

Киргизия (996)312-96-26-47

Новокузнецк (3843)20-46-81 Новосибирск (383)227-86-73 Омск (3812)21-46-40 Орел (4862)44-53-42 Оренбург (3532)37-68-04 Пенза (8412)22-31-16 Пермь (342)205-81-47 Ростов-на-Дону (863)308-18-15 Рязань (4912)46-61-64 Самара (846)206-03-16 Санкт-Петербург (812)309-46-40 Саратов (845)249-38-78 Севастополь (8692)22-31-93 Симферополь (3652)67-13-56

Казахстан (7172)727-132

Смоленск (4812)29-41-54 Сочи (862)225-72-31 Ставрополь (8652)20-65-13 Сургут (3462)77-98-35 Тверь (4822)63-31-35 Томск (3822)98-41-53 Тула (4872)74-02-29 Тюмень (3452)66-21-18 Ульяновск (8422)24-23-59 Уфа (347)229-48-12 Хабаровск (4212)92-98-04 Челябинск (351)202-03-61 Череповец (8202)49-02-64 Ярославль (4852)69-52-93

Россия (495)268-04-70

vyh@nt-rt.ru || https://vishay.nt-rt.ru/